



US006661035B2

(12) **United States Patent**
Negro et al.(10) **Patent No.:** US 6,661,035 B2
(45) **Date of Patent:** Dec. 9, 2003(54) **LASER DEVICE BASED ON SILICON NANOSTRUCTURES**(75) Inventors: **Luca Dal Negro**, Verona (IT); **Giorgia Franzo'**, San Giovanni La Punta (IT); **Zeno Gaburro**, Verona (IT); **Fabio Iacona**, Aci Castello (IT); **Lorenzo Pavesi**, Trento (IT); **Francesco Priolo**, San Giovanni La Punta (IT)(73) Assignees: **INFM Instituto Nazionale per la Fisica Della Materia**, Geneva (IT); **Universita'Degli Studi di Trento**, Trento (IT); **Universita'Degli Studi di Catania**, Catania (IT); **Consiglio Nazionale Della Ricerche**, Roma (IT)

(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

(21) Appl. No.: **09/989,456**(22) Filed: **Nov. 21, 2001**(65) **Prior Publication Data**

US 2002/0163003 A1 Nov. 7, 2002

(30) **Foreign Application Priority Data**

May 7, 2001 (IT) TO201A424

(51) **Int. Cl.⁷** **H01L 29/88; H01L 29/861; H01S 5/00; H01S 3/091**(52) **U.S. Cl.** **257/105; 372/43; 372/70**(58) **Field of Search** 372/43, 70; 257/103(56) **References Cited**

U.S. PATENT DOCUMENTS

5,757,837 A * 5/1998 Lim et al. 372/43

5,852,346 A 12/1998 Komoda et al.
6,067,307 A * 5/2000 Krishnamoorthy 372/26

OTHER PUBLICATIONS

Gritsenko et al., Silicon nanocluster in silicon nitride: PL, Raman scattering and ESR studies, vol. 8, 1997, pp. 196-199, IEEE.*

T. Baron et al, Silicon quantum dot nucleation on Si₃N₄, SiO₂ and SiOxNy substrates for nanoelectronic devices, Journal of Crystal growth, 209, (2000) 1004-1008.*

Streetman (Solid State Electronic Devices, 4th edition, pp. 384-390).*

L. Pavesi, et al., "Optical gain in silicon nanocrystals" Nature vol. 408, pp. 440-444, Nov. 2000.

K. D. Hirschman, et al., "Silicon-based visible light emitting devices integrated into microelectronic circuits" Nature, vol. 384, pp. 338-340, (1996).

L. T. Canham "Silicon quantum wire array fabrication by electrochemical and chemical dissolution of wafers", Appl. Phys. Lett., vol. 57, pp. 1045-1048, (1990).

* cited by examiner

Primary Examiner—Steven Loke

Assistant Examiner—Samuel A Gebremariam

(74) Attorney, Agent, or Firm—Sughrue Mion, PLLC

(57) **ABSTRACT**

A silicon-based light-emitting device is described and comprises an active region, an excitation system which can bring about a condition of inversion of the population of carriers within the active region, and semi-reflective elements which can define a resonant optical structure in which the active region is inserted so as to bring about stimulated emission of coherent light. The active region comprises silicon nanostructures immersed in a silicon-dioxide-based dielectric matrix.

23 Claims, 2 Drawing Sheets